

Amendments to the Specification:

Please amend the specification as follows:

Please replace the seventh paragraph starting at page 2, line 23, with the following rewritten paragraph:

FIGS. 2A and 2B are photographic views showing variation of ion density when voltage is applied to a dual grid assembly in a neutral beam etching device disclosed in the above patent. See Appendix A for a color version of these drawings;

Please replace paragraphs three and four under the heading "BRIEF DESCRIPTION OF THE DRAWINGS" at page 4, with the following rewritten paragraphs:

FIG. 2A is a photographic view showing ion density in the conventional ion beam source shown in FIG. 1. See Appendix A for a color version of this Figure;

FIG. 2B is a photographic view showing variation of voltage in the conventional ion beam source shown in FIG. 1. See Appendix A for a color version of this Figure;

Please replace the paragraphs beginning at page 4, line 25 through page 5, line 3 with the following rewritten paragraphs:

FIG. 5A is a photographic view showing ion density if a 3-grid neutral beam source according to one embodiment of the present invention. See Appendix A for a color version of this Figure;

FIG. 5B is a photographic view showing variation of voltage in a 3-grid neutral beam source according to one embodiment of the present invention. See Appendix A for a color version of this Figure;

Please replace the second to last paragraph on page 7, line 19, with the following rewritten paragraph:

FIGS. 5A and 5B are photographic views showing variation of ion density when voltage is applied to the 3-grid neutral beam ion source of the present invention. See Appendix A for color versions of these figures.